

Storage-Ring Vacuum Solution for the EXL Silicon Particle Array

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for the EXL collaboration

1) GSI Darmstadt, 2) KVI Groningen, 3) PTI St. Petersburg, 4) Universität Mainz, 5) TU Darmstadt

EMMI workshop

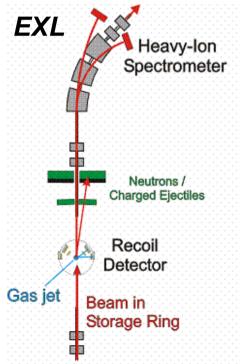
Physics Prospects at the ESR and HITRAP Eisenach June 27 – 30, 2010



EXL Project at FAIR

EXPERIMENT:

- Reactions with radioactive beams in inverse kinematics
- Recoil detector ESPA (EXL's Silicon Particle Array)
- Hundreds of DSSDs planned
- Placement in NESR environment



VACUUM REQUIREMENT:

- NESR vacuum better than 10⁻¹⁰ mbar
- Reasonable pumping-baking times after ESPA installation in NESR

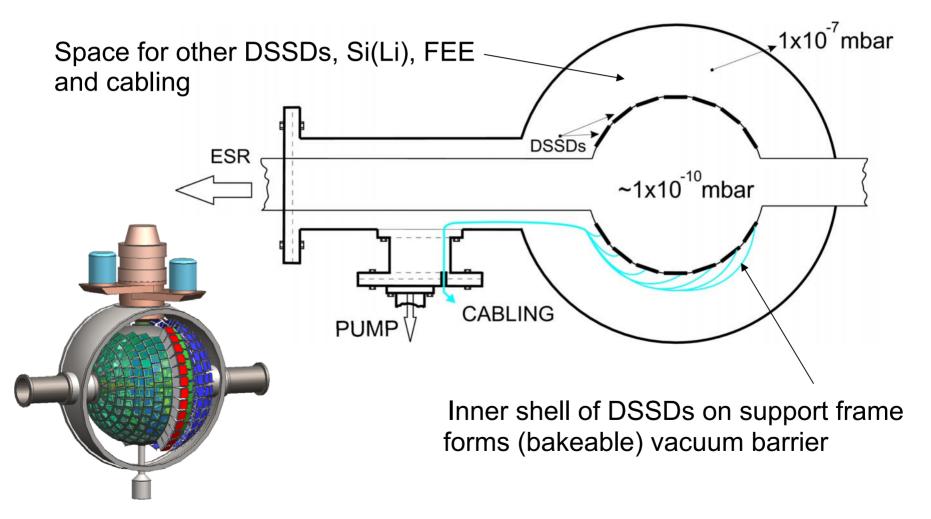
ESPA

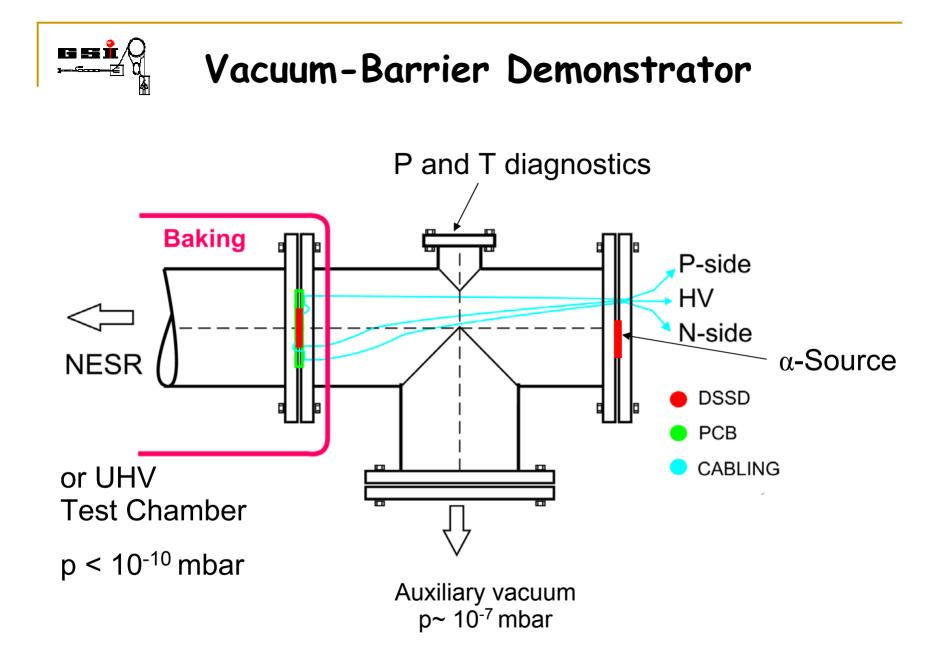
DEVELOPMENT:

• UHVacuum barrier prototype using DSSDs

Using DSSDs as High-Vacuum Barrier

• Differential pumping proposed to separate NESR vacuum from EXL instrumentation (cabling, FEE, other detectors)



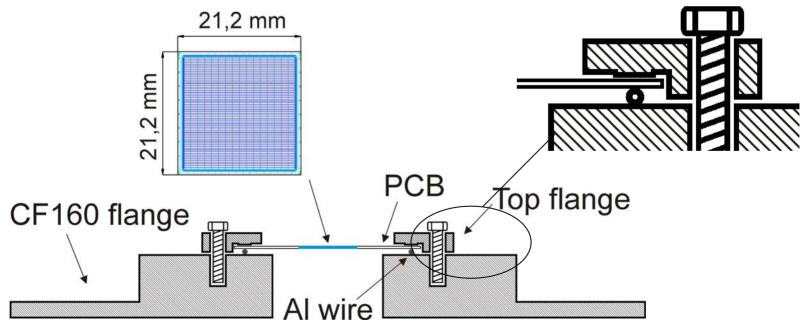


Requirements and Separation Principle

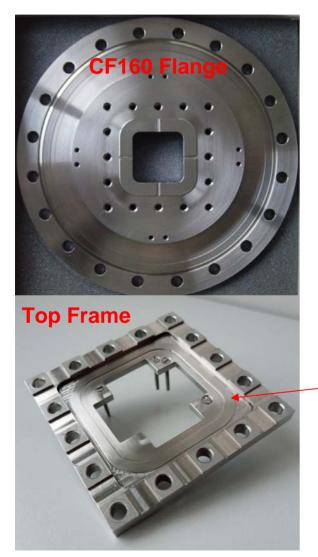
- PCB with one "clean" side no connectors, soldering etc.
 - Connections from one side of DSSD must be driven on the other side

Bakeability up to at least 200°C

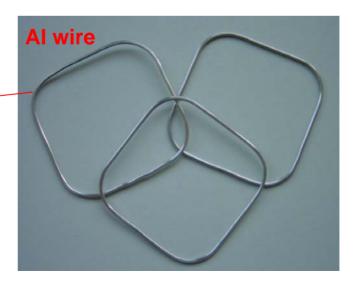
- Restricted choice of material
- Matched thermal expansion coefficients
- PCB should be easily replaceable from the frame



Mechanical Construction

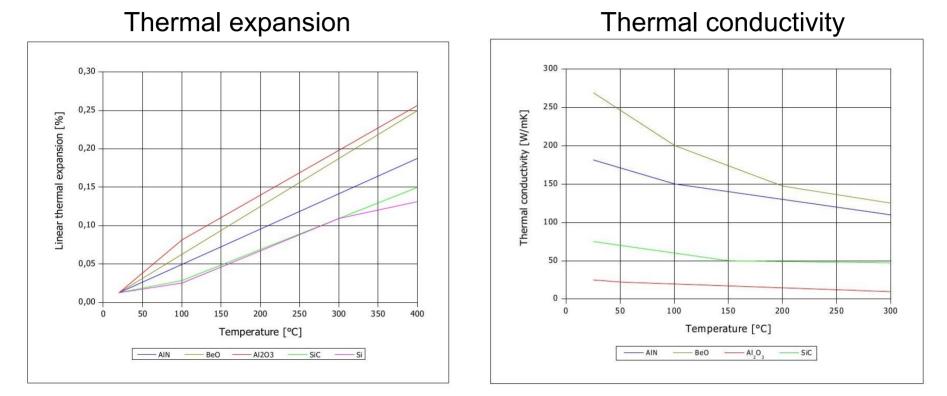


- Aluminium wire frame used as a vacuum seal
 Welded wire
- Base frame machined from CF160 flange
 - Houses Al wire on top of which PCB is placed
 - ${\scriptstyle \bullet}$ Has $\alpha {\rm -source}$ holder
- Top frame from stainless steal
 - Has groove that presses on PCB
 - Has mounts for connectors





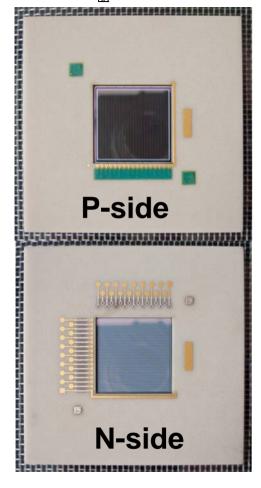
PCB Material Properties



IMPORTANT BAKING PARAMETERS:

- Thermal expansion of AIN fits best to Silicon (≈ 0.03% @ 200°C)
- AIN has high thermal conductivity (170 200) W/mK Silicon 160 W/mK

AIN Ceramic PCB and Connectors



PCB designed to have "through board" contacts

- Laser drilled holes for routing P-side contacts to N-side
- Holes hermetically filled and covered with glass
- Manufactured from Aluminum Nitride (AIN)
 - Ultra-low outgassing + bakeable to > 200°C
 - Expansion coefficient close to Silicon
 - High thermal conductivity
- DSSD glued with EPO-TEK®H77S low-outgassing

glue





Connectors machined from PEEK®

- Spring pins of 0.52 mm diameter used
- Kapton coated bakeable cables used



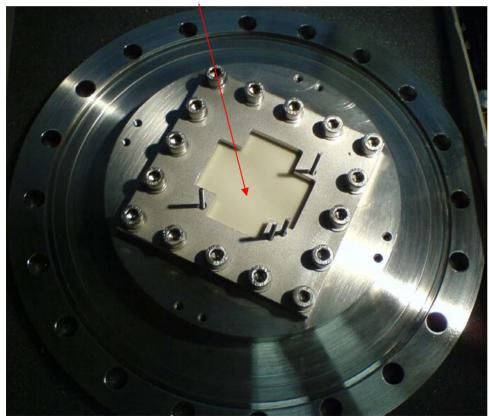


Blind PCB Vacuum Test

• Test of the AI wire tightness with the blind (no detector) PCB

• UHV side \rightarrow 5 * 10⁻¹⁰ mbar vs. Low-vacuum side \rightarrow 1 * 10⁻¹ mbar

Mounted blind PCB



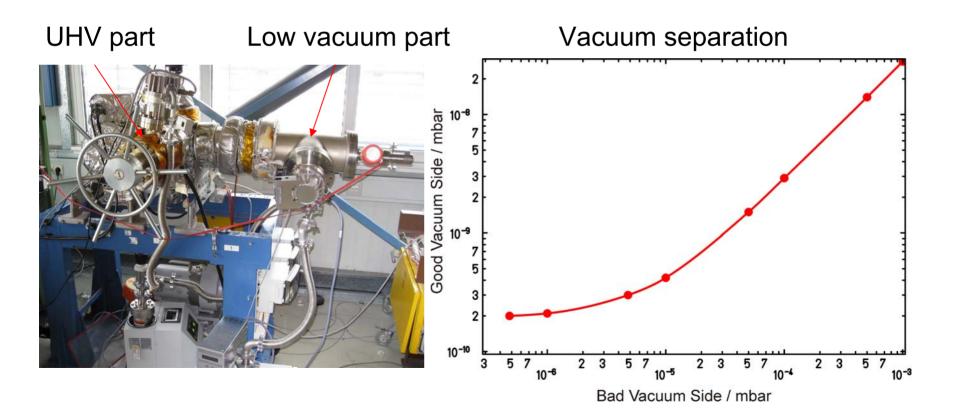
CONDITIONS:

- Low-vacuum side
 - Oil-free prepump
- High-vacuum side
 - Turbo pump
 - Baking for 3 days
 - Up to 200°C



Differential Vacuum Test

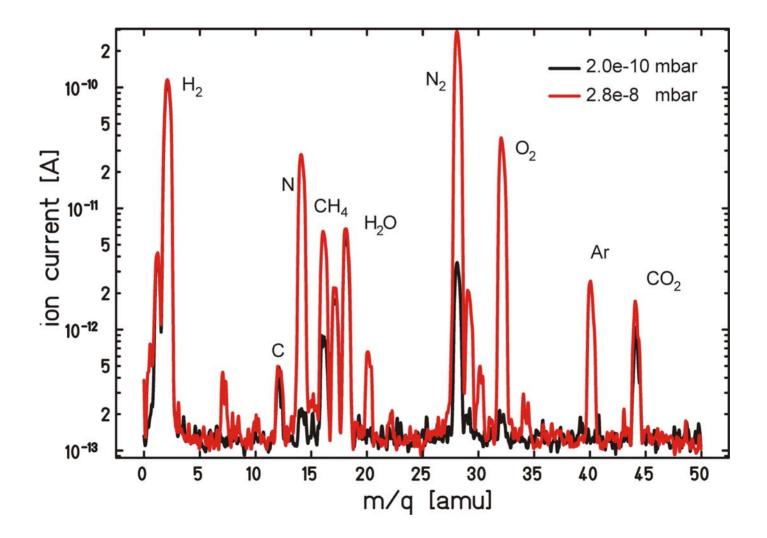
- Differential vacuum test using real DSSD as a vacuum barrier
 4 orders of magnitude difference between low and UH vacuum in wide pressure region
- Vacuum of **2** * **10**⁻¹⁰ mbar reached pumping limit of the station





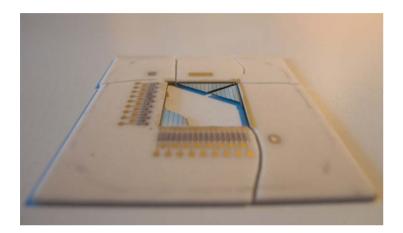
Outgassing Results

Low rate of outgassing and rest-gas spectra clear of contaminants for glued DSSD





Current Status



...from break to breakthrough?...

(Hair-line crack occurred during baking)

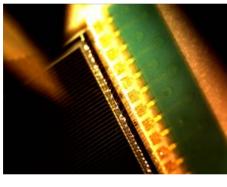
- ✓ DSSD detector on ceramic PCB constructed for vacuum test
- 9 orders of magnitudes of vacuum difference held by AI wire seal
- Vacuum separation by 4 orders of magnitudes in pressure reached using DSSD as vacuum window
- No vacuum deterioration by outgassing components



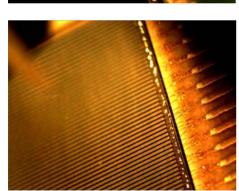
Next Steps

- Improve mechanical forces and reliability (double Alu-ring structure)
- Test a bonded DSSD (16 x 16 channels)

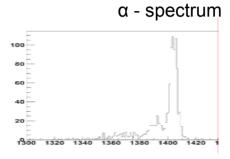




N-side



Performance Test

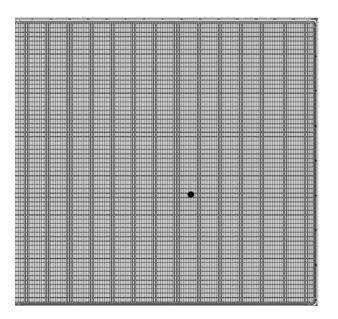






Outlook

- Optimizing the design to maximize active area
- Mechanical solutions other than demonstrator setup
- New ceramic PCB design for 6.5 x 6.5 cm² DSSDs (128 x 64 strips)



Silicon: 7 - 20 kOhm×cm <u>Diode structure:</u> p+ (strips) – i - n+ (strips), orthogonal, n+ - strip insulation by p+ implant <u>Diode area:</u> 65 x 65 mm² <u>Diode topology:</u> Strips on p+ side: 128 Strips on n+ side: 64 <u>Diode thickness:</u> 300 µm <u>Operational reverse voltage limit:</u> > 100 V



Thank You